



PATENT ABSTRACTS OF JAPAN

(11) Publication number: 05232689 A

(43) Date of publication of application: 10.09.1993

(51) Int. Cl. G03F 1/14

(21) Application number: 04033655

(71) Applicant: FUJITSU LTD

(22) Date of filing: 20.02.1992

(72) Inventor: MATSUYAMA TAKAYOSHI

(54) METHOD FOR BONDING PELLICLE,
PELLICLE AND MASK

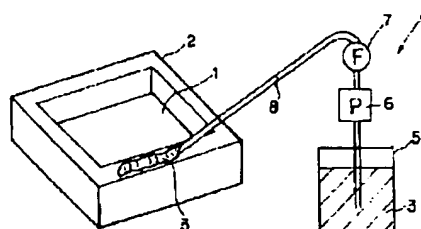
(57) Abstract:

PURPOSE: To provide a pellicle which can easily be exfoliated from a mask without contaminating or damaging them and can enhance the yield of semiconductor devices.

CONSTITUTION: One side of the frame member 2 of a pellicle with a pellicle film 1 stuck to the other side is coated with an adhesive member 3 which is dissolved in a solvent and a mask is bonded to the pellicle with

the adhesive member 3 so that at least a face of the mask with a formed mask pattern is covered with the pellicle.

COPYRIGHT: (C)1993,JPO&Japio



Reference 1: Japanese Patent Application Laid Open No. S62-288842

Title of the Invention: Protective Dustproof Body for Photomask or Reticle

Filing Date: June 9, 1986

Applicant: Tosoh Corporation

Extract:

Claim describes a protective dustproof body for photomasks or reticles, which is a transparent thin cover made of synthetic quartz glass disposed at a constant distance from the surface of a substrate.